



HYBRID PULSED LASER DEPOSITION OF COMPLEX OXIDE THIN FILMS MADE FROM ELEMENTS HAVING A LARGE VAPOR PRESSURE MISMATCH

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WARF: P230036US01

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The Invention

UW-Madison researchers have developed a new synthesis method, hybrid PLD (Pulsed Laser Deposition), that synergistically combines the advantages of thermal evaporation and conventional PLD to overcome the present roadblocks to creating volatility mismatched thin film materials. In this system, the volatile species is supplied with thermal evaporation, and the non-volatile species with laser ablation, solving the longstanding challenge of accurate stoichiometry and defect control in compounds with mixed volatility constituents.

Additional Information

For More Information About the Inventors

- [Chang-Beom Eom](#)

Publications

- [Read a news story about this technology.](#)

Tech Fields

- [Semiconductors & Integrated Circuits : Design & fabrication](#)

For current licensing status, please contact Michael Carey at mcarey@warf.org or 608-960-9867